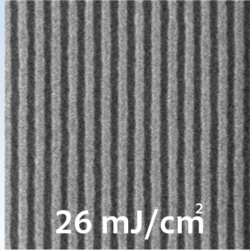
JSR EUV Photoresist

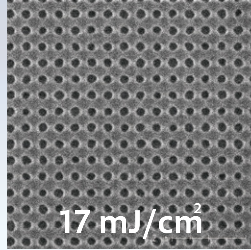
Challenge for Sensitivity and Defectivity

15 nm L/S



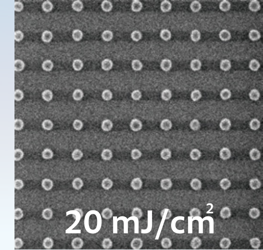
Substrate: Organic HM
Resist FT: 35 nm

21 nm C/H

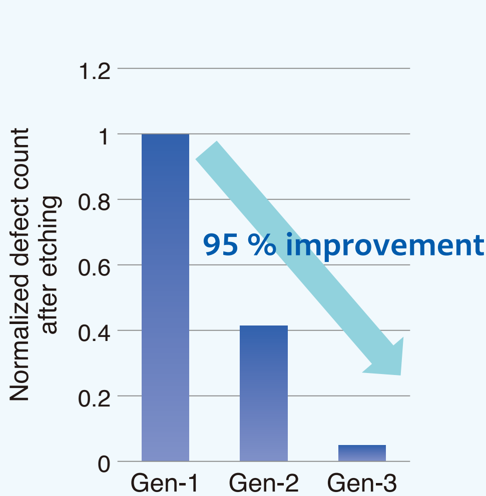


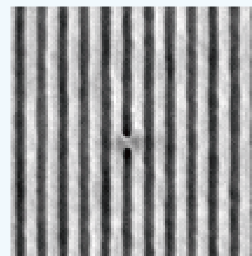
Substrate: ML/Organic HM
Resist FT: 50 nm

21 nm Pillar



Substrate: ML/Organic HM
Resist FT: 50 nm



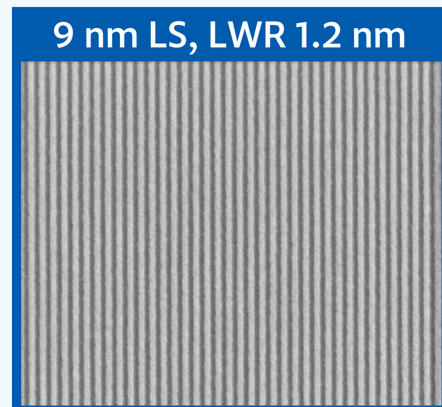


Target CD: 18 nm LS
Exposure: NXE3300 (NA0.33)

Challenge for Next Generation Photoresist

inpria Corporation

Development and manufacturing of "metal-based EUV resists"



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